

FORM PTO-1449 (Modified)		Attorney Docket No.: A524R1/T289		Application No.: 09/187,551	
LIST OF PATENTS AND PUBLICATIONS FOR APPLICANT'S INFORMATION DISCLOSURE STATEMENT (Use several sheets if necessary)		Applicant: MUSAKA et al.			
		Filing Date: November 5, 1998		Group: 1762	
Reference Designation		U.S. PATENT DOCUMENTS			Page 1
Examiner Initial	Document No.	Date	Name	Class	Filing Date (If Appropriate)
AA	5,483,636	01/09/96	Saxena	395	03/29/95
AB	5,750,211	05/12/98	Weise et al.	427	07/16/93

FOREIGN PATENT DOCUMENTS						
	Document No.	Date	Country	Class	Sub-class	Translation (Yes/No)
AC	0 666 340 A1	08/09/95	EP	C23C 16/44	C23C 16/52	in English Yes
AD	0 724 286 A1	07/31/96	EP	H01L 21/316	C23C 16/40	in English Yes
AE	07-29975	01/31/95	JP	H01L 21/768	H01L 21/205	Yes (abstract)
OTHER ART (Including Abstracts, Title, Date, Pertinent Pages, Etc.)						
AF	Bazylenko, M.V. et al., "Pure And Fluorine-Doped Silica Films Deposited In A Hollow Cathode Reactor For Integrated Optic Applications", J. Vac. Sci. Technol. A 14(2), Mar/Apr 1996, pp. 336-345.					
AG	Mizuno et al., "Dielectric Constant and Stability of Fluorine Doped PECVD Silicon Oxide Thin Films", Thin Solid Films 283 (1996) pp. 30-36. Sept.					
EXAMINER	DATE CONSIDERED		3/15/00			

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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